

ABSTRACT

PHOTOACID GENERATOR, COPOLYMER, CHEMICALLY AMPLIFIED RESIST COMPOSITION, AND METHOD OF FORMING PATTERN USING THE CHEMICALLY AMPLIFIED RESIST COMPOSITION

Disclosed are a photoacid generator, a copolymer, a chemically amplified resist composition, and a method of forming a pattern using the chemically amplified resist composition. The photoacid is connected with a main chain of the copolymer, whereby the photoacid is equally dispersed within a resist layer, and characteristics of line edge roughness of a resist pattern is improved.

No figure



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